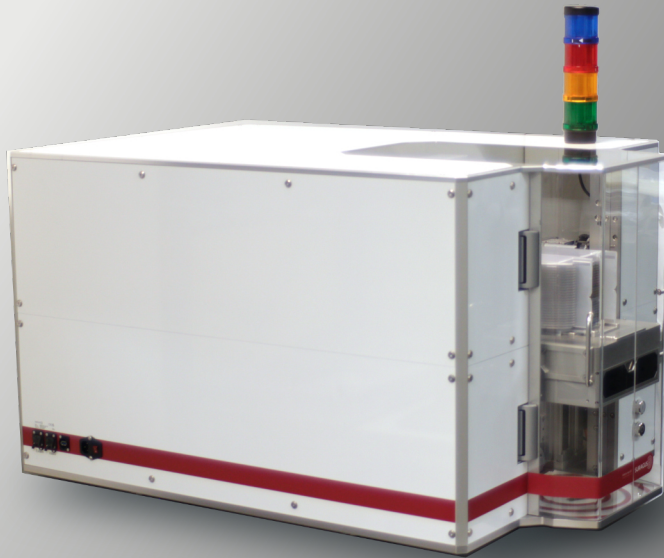


EddyCus[®] ResMapper – Automated Non-contact Wafer Imaging Device P_C2C_28



Highlights

- ▶ Non-contact
- ▶ Edge grip only
- ▶ Automated wafer handling
- ▶ Fast (one measurement within 60 seconds)
- ▶ High resolution (5 to 22,000 points/wafer)
- ▶ Repeatable and accurate
- ▶ Customized setups

Applications

- ▶ Wafer characterization
- ▶ Layer deposition (PVD, CVD, plating ...)
- ▶ Epitaxy
- ▶ Implantation
- ▶ Doping
- ▶ Annealing
- ▶ Laser irradiation
- ▶ Etching
- ▶ Machining and polishing
- ▶ Wafer sorting
- ▶ (De)-oxidation
- ▶ Defect imaging
- ▶ Final inspection

Parameters

- ▶ Resistivity [mOhm-cm]
- ▶ 2D wafer thickness [μm]
- ▶ Sheet resistance [Ohm/sq]
- ▶ Metal layer thickness [nm, μm]
- ▶ Total thickness variation (TTV) [μm]
- ▶ Defect and integrity assessment
- ▶ 1D, 2D bow and warpage [μm]
- ▶ Wafer diameter [mm]

Materials


- ▶ Semiconductors e.g.
 - ▶ Si
 - ▶ SiC
 - ▶ GaAs
 - ▶ GaN
- ▶ Metal films e.g.
 - ▶ Al
 - ▶ Au
 - ▶ Ti
 - ▶ Cu
- ▶ Other conductive films and materials

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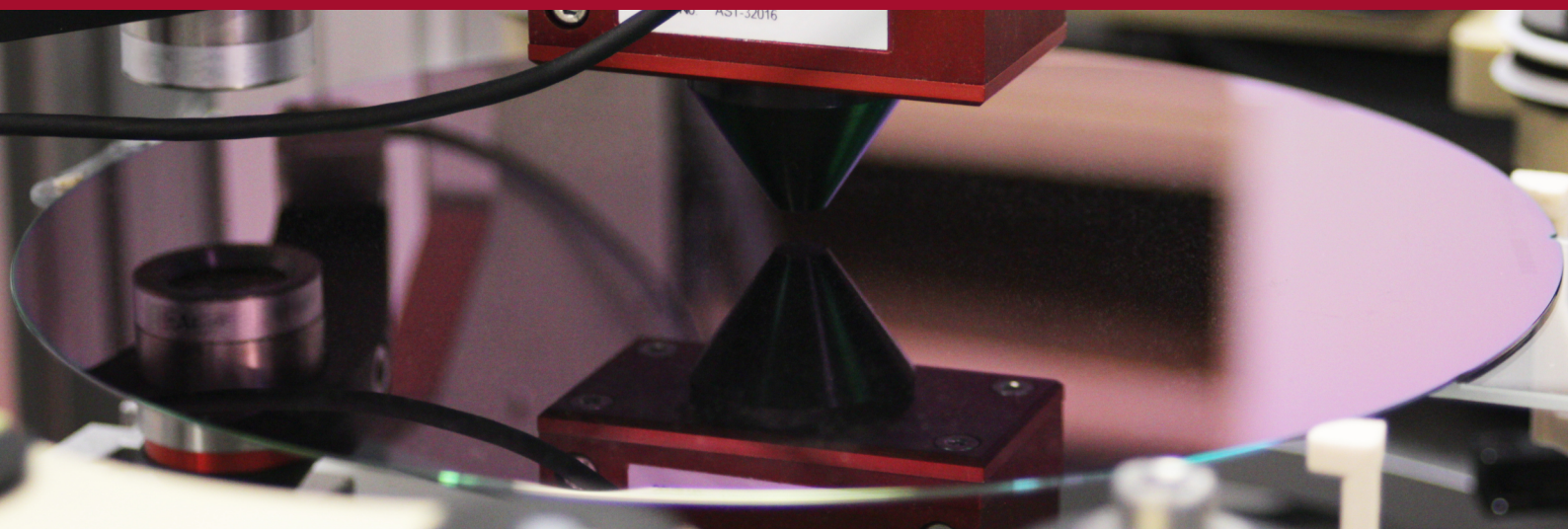
For further questions:
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Visit us at:
www.suragus.com
www.suragus.com/calculator
www.suragus.com/EddyCusResMapper

Engineered and Made in Germany 





Measurement technology	Non-contact high frequency eddy current sensor, Confocal sensor for TTV, warpage and bow	
Substrates	150 and 200 mm wafer	
Wafer thickness range	300 – 1,000 μm (other on request)	
Cassettes	1	
Edge effect correction / exclusion	2 – 10 mm (depending on size, range, setup and requirements)	
Resistivity range	0.1 – 1,000 mOhm-cm	< 1 – 3 % accuracy
Sheet resistance range	0.0001 – 100,000 Ohm/sq	< 1 – 3 % accuracy
Metal layer thickness conversion	Range e. g. for Aluminum: 27 nm – 27 μm	
Features	Total thickness variation, Warpage Carrier ID reader, customized data interface, API for customer software integration	
Measurement patterns	Standard ~ 22 000 points Points 9 / 17 / 49 / 81 / 99 / 169 / 625 / / 100,000	
Measurement time	30 – 90 s per wafer depending on measurement points	
Throughput	45 wafers per hour (~ 22 000 measurement points per wafer)	
Device dimensions (w/d/h)	785 mm x 1,170 mm x 666 mm / 30.91" x 46.06" x 26.22"	

Software and Handling

- ▶ Web Interface
- ▶ Easy to use software
- ▶ Recipe Management to adjust thresholds, data processing pipelines, result export options and more
- ▶ Display of mapping with intuitive graphical analysis tools
- ▶ Access Level for user profiles
- ▶ Extensive Job Management
 - ▶ Creation of default jobs for 150 and 200mm
 - ▶ Freely customizable sequence Jobs
 - ▶ Single Wafer analysis
- ▶ Result download via Webpage / API / FTP (future) / SECS-GEM (extrem future)
- ▶ Creation of statistics for mappings and thickness measurements

